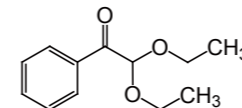


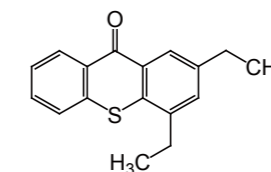
131709



6175-45-7

2,2-Diethoxyacetophenone, 97%

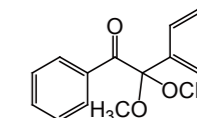
105216



82799-44-8

2,4-Diethyl-9H-thioxanthen-9-one, 98%

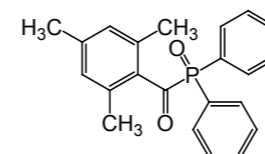
543244



24650-42-8

2,2-Dimethoxy-2-phenylacetophenone, 98%

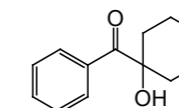
567999



75980-60-8

Diphenyl(2,4,6-trimethylbenzoyl) phosphine oxide, 99%

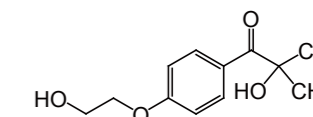
330139



947-19-3

1-Hydroxycyclohexyl phenyl ketone, 99%

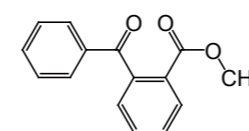
511601



106797-53-9

2-Hydroxy-4'-(2-hydroxyethoxy)-2-methylpropiophenone, 99%

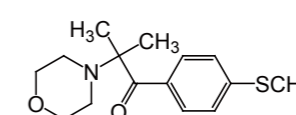
342981



606-28-0

Methyl 2-benzoylbenzoate, 99%

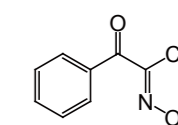
506402



71868-10-5

2-Methyl-4'-(methylthio)-2-morpholinopropiophenone, 99%

307788



119-51-7

1-Phenyl-1,2-propanedione-2-oxime, 99%

Reagents for Photoresists Synthesis

jk-scientific.com

J&K Scientific bvba(Belgium)

T: +32 11 340 390

F: +32 11 793 917

E: jkeu@jk-scientific.com

J&K Scientific LLC(USA)

T: +1 952 942 3333

F: +1 952 942 3322

E: jkus@jk-scientific.com

J&K Scientific Ltd(China)

T: +86 10 8284 8833

F: +86 10 8284 9933

E: info@jk-scientific.com

J&K Scientific Ltd(Hong Kong)

T: +852 2810 5022

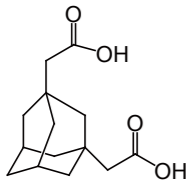
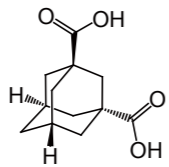
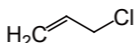
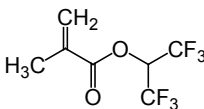
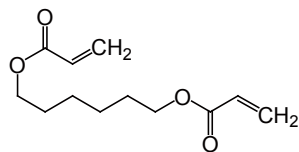
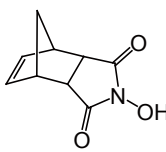
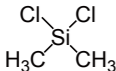
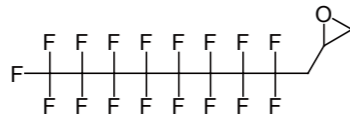
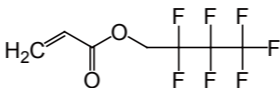
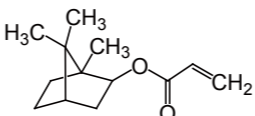
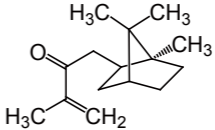
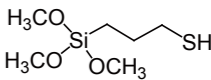
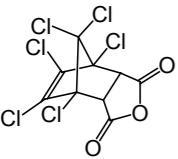
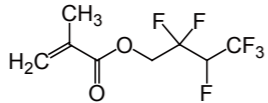
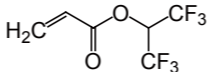
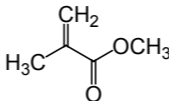
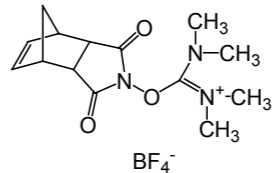
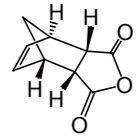
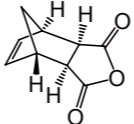
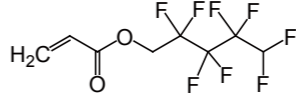
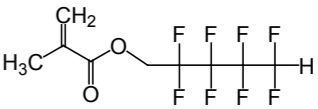
F: +852 2810 5033

E: info@jk-scientific.com

Reagents for Photoresists Synthesis

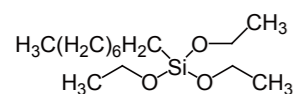
Photoresists are widely used in integrated circuits, semiconductor devices, touch screens and photovoltaic materials. As a professional supplier, J&K provides a variety of reagents for the synthesis of photoresists. Our products offer reliable quality and high performance and are available in different package sizes from grams to kilograms to meet your requirements from basic research to large-scale manufacturing.

■ Monomers for Photoresists

<p>476032</p>  <p>17768-28-4 1,3-Adamantandiacetic acid, 97%</p>	<p>380913</p>  <p>39269-10-8 1,3-Adamantedicarboxylic acid, 97%</p>	<p>488389</p>  <p>107-05-1 Allyl chloride, 98%, stabilized</p>	<p>472949</p>  <p>3063-94-3 1,1,1,3,3,3-Hexafluoroisopropyl methacrylate, 99%</p>	<p>118591</p>  <p>13048-33-4 1,6-Hexanediol diacrylate, 88%, stabilized with 100 ppm HQ</p>	<p>127777</p>  <p>21715-90-2 N-Hydroxy-5-norbornene-2,3-dicarboxylic acid imide, 98%</p>
<p>191866</p>  <p>75-78-5 Dichlorodimethylsilane, 99.3%</p>	<p>135611</p>  <p>38565-53-6 1,2-Epoxy-1H,1H,2H,3H,3H-heptafluoroundecane, 96%</p>	<p>346365</p>  <p>424-64-6 2,2,3,3,4,4,4-Heptafluorobutyl acrylate, 97%</p>	<p>396012</p>  <p>5888-33-5 Isobornyl methacrylate, 93%, stabilized with 200 - 400 ppm MEHQ</p>	<p>283272</p>  <p>7534-94-3 Isobornyl methacrylate, 90%, stabilized with 150 ppm MEHQ</p>	<p>180573</p>  <p>4420-74-0 3-Mercaptopropyltrimethoxysilane, 97%</p>
<p>313268</p>  <p>115-27-5 1,4,5,6,7,7-Hexachloro-5-norbornene-2,3-dicarboxylic anhydride, 96%</p>	<p>289722</p>  <p>36405-47-7 2,2,3,4,4,4-Hexafluorobutyl methacrylate, 98%</p>	<p>443905</p>  <p>2160-89-6 1,1,1,3,3,3-Hexafluoroisopropyl acrylate, 99%, stabilized with MEHQ</p>	<p>153563</p>  <p>80-62-6 Methyl methacrylate, 99%</p>	<p>253208</p>  <p>125700-73-4 O-(5-Norbornene-2,3-dicarboximido)-N,N,N',N'-tetramethyluronium tetrafluoroborate, 98%</p>	<p>325921</p>  <p>129-64-6 cis-5-Norbornene-endo-2,3-dicarboxylic anhydride, 97%</p>
<p>609785</p>  <p>2746-19-2 cis-5-Norbornene-exo-2,3-dicarboxylic anhydride, 96%</p>	<p>950939</p>  <p>376-84-1 2,2,3,3,4,4,5,5-Octafluoropentyl methacrylate, 98%, stabilized with MEHQ</p>	<p>187072</p>  <p>355-93-1 2,2,3,3,4,4,5,5-Octafluoropentyl methacrylate, 98%</p>			

Reagents for Photoresists Synthesis

339028



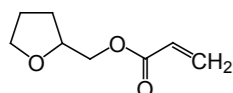
2943-75-1
n-Octyltriethoxysilane, 97%

130690



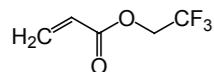
17527-29-6
1H,1H,2H,2H-Perfluorooctyl acrylate, 95%

999070



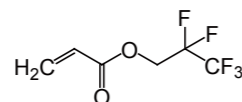
2399-48-6
Tetrahydrofurfuryl acrylate, 98%, stabilized with MEHQ

364648



407-47-6
2,2,2-Trifluoroethyl acrylate, 98%, stabilized with 200 ppm MEHQ

136430



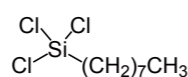
356-86-5
2,2,3,3,3-Pentafluoropropyl acrylate, 97%

449033



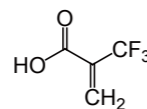
1996-88-9
2-(Perfluorooctyl)ethyl methacrylate, 97%

953647



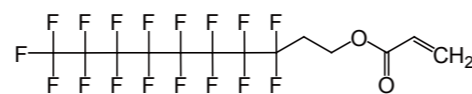
5283-66-9
Trichloro(octyl)silane, 98%

154404



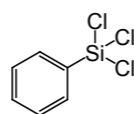
381-98-6
2-(Trifluoromethyl)acrylic acid, 98%

947577



27905-45-9
1H,1H,2H,2H-Perfluorodecyl acrylate, 97%, stabilized with 70 ppm BHT, 15 ppm TBC

580706



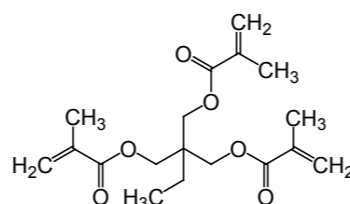
98-13-5
Phenyltrichlorosilane, 98%

549606



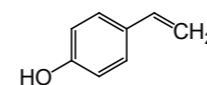
78560-45-9
Trichloro(1H,1H,2H,2H-perfluorooctyl)silane, 97%

496960



3290-92-4
Trimethylolpropane trimethacrylate, 90%

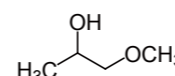
441305



2628-17-3
4-Vinylphenol, 95%, 10 wt.% solution in propylene glycol

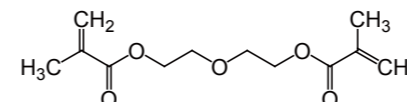
■ Additives for Photoresists

152163



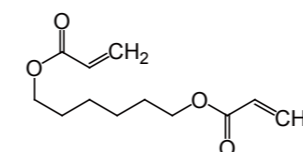
107-98-2
2-Acetoxy-1-methoxypropane, mixture of isomers, 99.5%

277526



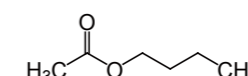
2358-84-1
Di(ethylene glycol) dimethacrylate, 95%

118591



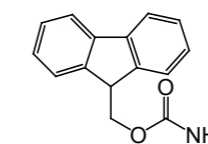
13048-33-4
1,6-Hexanediol diacrylate, 88%, stabilized with 100 ppm HQ

908824



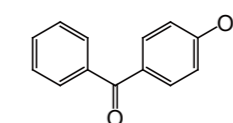
123-86-4
n-Butyl acetate, 99%

277506



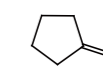
84418-43-9
9-Fluorenylmethyl carbamate, 98%

277043



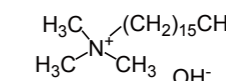
1137-42-4
4-Hydroxybenzophenone, 99%

246925



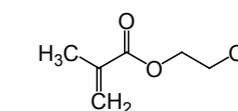
120-92-3
Cyclopentanone, 99.5%

215000



505-86-2
Hexadecyltrimethylammonium hydroxide, 25% in methanol

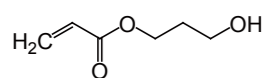
126667



868-77-9
2-Hydroxyethyl methacrylate, 99%

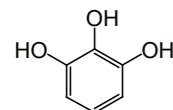
Reagents for Photoresists Synthesis

620524



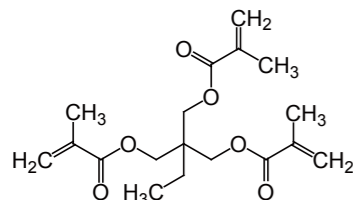
25584-83-2
Hydroxypropyl acrylate, 96%, mixture of 2-Hydroxypropyl and 2-Hydroxy-1-methylethyl acrylate

193900



87-66-1
1,2,3-Trihydroxybenzene, 99%

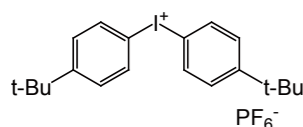
496960



3290-92-4
Trimethylolpropane trimethacrylate, 90%

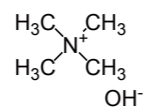
■ Photoacid Generators

177582



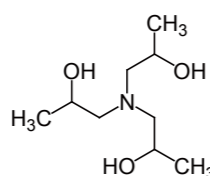
61358-25-6
Bis(4-tert-butylphenyl)iodonium hexafluorophosphate, 98%

457936



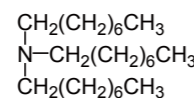
75-59-2
Tetramethylammonium hydroxide, 25% solution in H₂O

213496



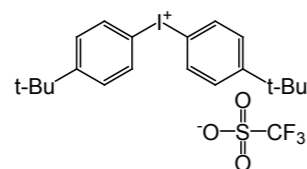
122-20-3
Triisopropanolamine, 99%, mixture of isomers

136152



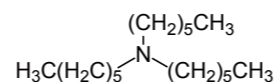
1116-76-3
Trioctylamine, 97%

512472



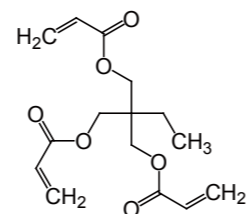
84563-54-2
Bis(4-tert-butylphenyl)iodonium triflate, 98%

283288



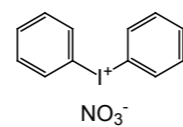
102-86-3
Trihexylamine, 98%

992571



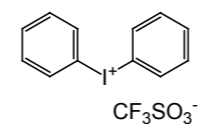
15625-89-5
Trimethylolpropane triacrylate, 85%, stabilized with MEHQ

517519



722-56-5
Diphenyliodonium nitrate, 97%

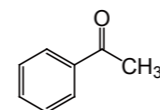
485359



66003-76-7
Diphenyliodonium triflate, 98%

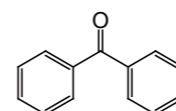
■ Photoinitiator for Photoresists

167389



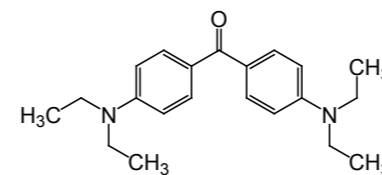
98-86-2
Acetophenone, 98%

248099



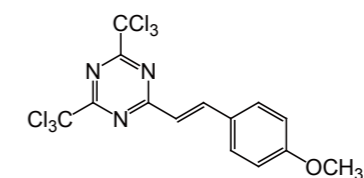
119-61-9
Benzophenone, 99%

606200



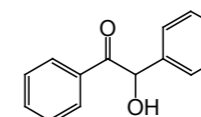
90-93-7
4,4'-Bis(diethylamino)benzophenone, 99%

305170



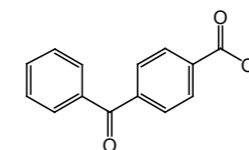
42573-57-9
2-(4-Methoxystyryl)-4,6-bis(trichloromethyl)-1,3,5-triazine, 98%

438305



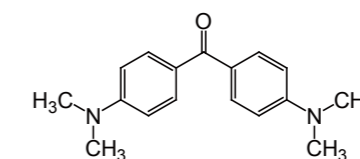
119-53-9
Benzoin, 98%

339349



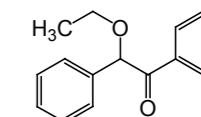
611-95-0
4-Benzoylbenzoic acid, 99%

278244



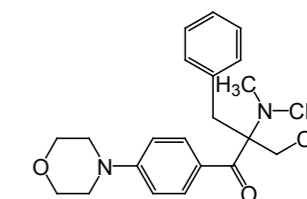
90-94-8
4,4'-Bis(dimethylamino)benzophenone, 98%

319287



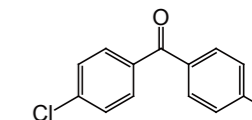
574-09-4
Benzoin ethyl ether, 99%

124965



119313-12-1
2-Benzyl-2-(dimethylamino)-4'-morpholinobutyrophenone, 97.5%

125941



90-98-2
4,4'-Dichlorobenzophenone, 99%